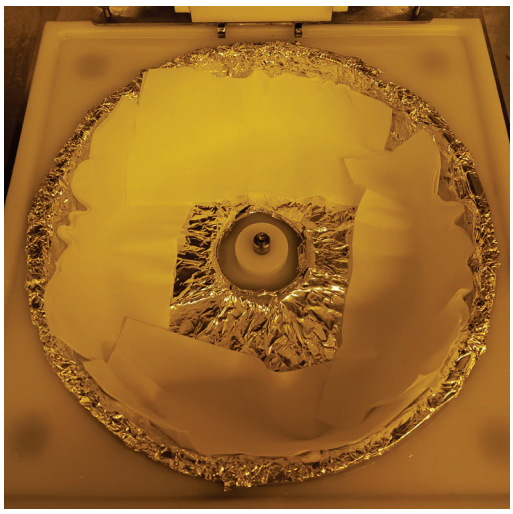
Clean Up FAQs



Thick resist in SPN-08 is so hard to clean up! What do I do?

Before running the recipe, lay wipes down around the sides and bottom of the liner. This should catch the bulk of the resist. Afterwards, remove the liner from the spinner before removing the wipes to keep the spindle clean. Don't forget to wipe down everything else!

After running multiple wafers, the resist dries up and it's harder to clean in the 5min you promised! Can I just leave it as is?

The cleaning guideline of ~2-5min only applies to a single coat of one wafer. If acetone-soluble resist, it will come out, just with some extra elbow grease. To avoid this, wipe down the spinner between wafers and/or place wipes in the liner to shorten the final cleanup step.

My resist seems to be glued to SPN-03 after spinning a bilayer with LOR. Help!

LOR/PMGI are not acetone soluble and will be resistant to regular cleanup steps. Before using the acetone-soluble imaging resist, wipe down the spinner (lid + bowl + liner) with IPA. This is much easier if the resist is still wet. If the resist is dry, it can start to flake off if you work at it. If the resist is particularly difficult to remove, report on NEMO.

I used to put aluminum foil in the spinners before, can I still do that?

This is not generally approved due to the potential of foil getting caught in the spindle as well as the volume of waste generated. Please use one of the other recommended methods or contact staff.